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(54) Title: LITHOGRAPHIC SYSTEM

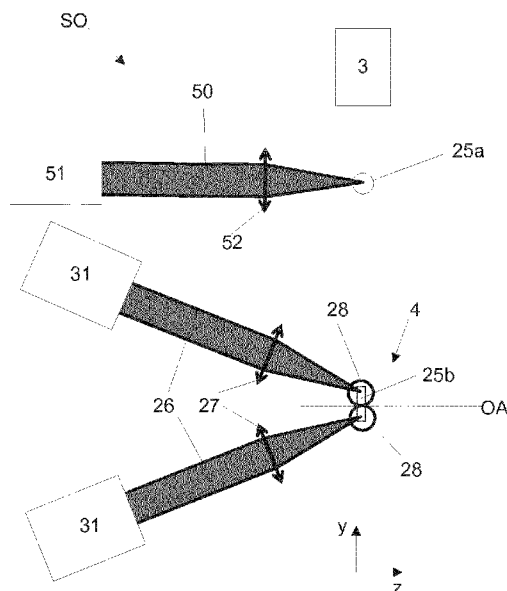


FIG. 4a

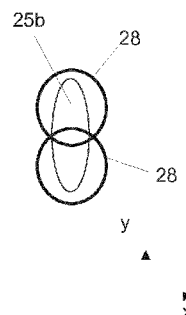


FIG. 4b

(57) **Abstract:** A lithographic system comprising a lithographic apparatus with an anamorphic projection system, and a radiation source configured to generate an EUV radiation emitting plasma at a plasma formation location, the EUV radiation emitting plasma having an elongate form in a plane substantially perpendicular to an optical axis of the radiation source.



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